L	Hits	Search Text	DB	Time stamp
Number				
1	339	((348/300) or (348/301) or	USPAT	2003/01/15
	1504	(348/308)).CCLS.		13:28
_	1504	(250/208.1).CCLS.	USPAT	2003/01/15
	. 67	hatano-keisuke\$.in.	USPAT	13:28   2002/12/18
_		nakashiba-yasutaka\$.in.	USPAI	09:59
_	229	((250/208.1).CCLS.) and (insulat\$3 adj	USPAT	2003/01/13
		(film\$1 or layer\$1)) same electrode\$1		08:25
_	38	((250/208.1).CCLS.) and (insulat\$3 adj	USPAT	2002/12/18
		(film\$1 or layer\$1)) same electrode\$1		10:56
		same isolat\$3		
-	38	((250/208.1).CCLS.) and (insulat\$3 adj	USPAT	2003/01/13
		(film\$1 or layer\$1)) same electrode\$1		13:12
		same isolat\$4	HCDAM	2002/01/12
_	9	((250/214.1).CCLS.) and (insulat\$3 adj (film\$1 or layer\$1)) same electrode\$1	USPAT	2003/01/13 13:31
		same isolat\$4		13:31
_	38	1	USPAT	2003/01/13
	30	(film\$1 or layer\$1)) same electrode\$1	ODIAI	13:34
		same isolat\$4		10.01
_	7	(((250/214.1).CCLS.) and (insulat\$3 adj	USPAT	2003/01/13
		(film\$1 or layer\$1)) same electrode\$1		13:13
	1	same isolat\$4) not (((250/208.1).CCLS.)		
		and (insulat\$3 adj (film\$1 or layer\$1))		
	_	same electrode\$1 same isolat\$4 )		0000/01/10
_	4	((250/214r).CCLS.) and (insulat\$3 adj	USPAT	2003/01/13 13:32
		(film\$1 or layer\$1)) same electrode\$1 same isolat\$4		13:32
_	2	(((250/214r).CCLS.) and (insulat\$3 adj	USPAT	2003/01/13
		(film\$1 or layer\$1)) same electrode\$1	OBITH	13:32
		same isolat\$4) not (((250/208.1).CCLS.)		
		and (insulat\$3 adj (film\$1 or layer\$1))		
		same electrode\$1 same isolat\$4 )		
-	17	(insulat\$3 adj (film\$1 or layer\$1)) same	USPAT	2003/01/13
		isolat\$4 near2 electrode\$1 and		13:45
		250/\$.ccls.	,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	2002/01/15
_	630	(insulat\$3 adj (film\$1 or layer\$1)) same isolat\$4 near2 electrode\$1 and	USPAT	2003/01/15
		257/\$.ccls.		09.30
_	624		USPAT	2003/01/13
	024	isolat\$4 near2 electrode\$1 and		13:46
		257/\$.ccls.) not ((insulat\$3 adj (film\$1		
		or layer\$1)) same isolat\$4 near2		
		electrode\$1 and 250/\$.ccls.)		
-	624		USPAT	2003/01/14
		same isolat\$4 near2 electrode\$1 and		14:20
		257/\$.ccls.) not ((insulat\$3 adj (film\$1		
		or layer\$1)) same isolat\$4 near2 electrode\$1 and 250/\$.ccls.)) not		
		(((250/208.1).CCLS.) and (insulat\$3 adj		
		(film\$1 or layer\$1)) same electrode\$1		
1		same isolat\$4 )		
-	5	("4751559"   "4812869"   "5010245"	USPAT	2003/01/14
		"5029998"   "5483318").PN.		10:30
_	1984	,	USPAT	2003/01/14
	_	silicide	HCDAT	14:33
-	3		USPAT	14:42
	_	with voltage\$1   (isolat\$3 adj electrode\$1) with constant	EPO; JPO;	2003/01/14
-	0	with voltage\$1	DERWENT;	14:42
		with vortagevi	IBM TDB	
_	28	(isolat\$3 adj electrode\$1) with voltage\$1	EPO; JPO;	2003/01/14
		(	DERWENT;	14:49
			IBM_TDB	
-	13	sasaki-michio\$.in.	USPAT	2003/01/14
				14:49
-	0	insulat\$3 same flow\$3 same heat\$3 same	USPAT	2003/01/15
		electrode\$1 same flatten\$3 same etch\$3		07:59
		same bury\$3	1	1

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-	1	insulat\$3 same heat\$3 same electrode\$1	USPAT	2003/01/15
İ		same flatten\$3 same etch\$3 same bury\$3		08:00
_	9	insulat\$3 same heat\$3 same flatten\$3 same	USPAT	2003/01/15
		etch\$3 same bury\$3		08:07
-	1	insulat\$3 same heat\$3 same flatten\$3 same	USPAT	2003/01/15
		etch\$3 same (bury\$3 or buried) same		08:07
		electrode\$1		
-	8	insulat\$3 same heat\$3 same flatten\$3 same	EPO; JPO;	2003/01/15
		etch\$3 same (bury\$3 or buried) same	DERWENT;	08:10
		electrode\$1	IBM TDB	
_	3	insulat\$3 same heat\$3 same flatten\$3 same	USPAT	2003/01/15
		(bury\$3 or buried) same electrode\$1		08:12
-	15	insulat\$3 same heat\$3 same flatten\$3 same	EPO; JPO;	2003/01/15
		(bury\$3 or buried) same electrode\$1	DERWENT;	08:24
			IBM TDB	
-	133	insulat\$3 with (bury\$3 or buried) same	USPAT	2003/01/15
		electrode\$1 same heat\$3		08:24
-	26	insulat\$3 with (bury\$3 or buried) same	USPAT	2003/01/15
		electrode\$1 same heat\$3 and flatten\$3		08:25
_	15	insulat\$3 with (bury\$3 or buried) same	USPAT	2003/01/15
		electrode\$1 same heat\$3 and flatten\$3		08:29
		same heat\$3		
-	4	insulat\$3 with (bury\$3 or buried) with	USPAT	2003/01/15
		(flow\$3 or heat\$3) same electrode\$1 and		08:31
		flatten\$3 with heat\$3		1
_	130	insulat\$3 with (flow\$3 or heat\$3) same	USPAT	2003/01/15
	_	electrode\$1 and flatten\$3 with heat\$3		08:31
-	5	insulat\$3 with (flow\$3 with heat\$3) same	USPAT	2003/01/15
		electrode\$1 and flatten\$3 with heat\$3		08:46
-	35	(insulat\$3 or bpsg) with (reflow\$3) same	USPAT	2003/01/15
		electrode\$1 and (flatten\$3 or flat) with		08:48
		heat\$3		
-	23	(insulat\$3 adj (film\$1 or layer\$1)) same	USPAT	2003/01/15
		isolat\$4 near2 electrode\$1 and		09:31
	[]	348/\$.ccls.		